## DS - 07/12/2 PLECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention

HIGH PRESSURE PROCESSING CHAMBER FOR A SEMICONDUCTOR WAFER

Application Number:

10/680783

5859

Confirmation Number:

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First Named Applicant:

William Jones

Attorney Docket Number:

Art Unit: Examiner:

Search string:

(6264752).pn

<u>Certification:</u> This Information Disclosure Statement was submitted under the following conditions, which satisfies the requirement under 37 CFR 1.97(e). The filer certified:

That each item of information contained in the information disclosure statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of the information disclosure statement.

## **US Patent Documents**

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
M	1	6264752	2001-07-24	Curtis et al.		118	729

Signature 2007

Examiner Name	Date
1 mhl	12124/06